

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

NISHIMOTO et al

Serial No.: 08/897,839

Filed: July 21, 1997

For: STRESS-ADJUSTED INSULATING
FILM FORMING METHOD,
SEMICONDUCTOR DEVICE AND
METHOD OF MANUFACTURING THE
SAME



Group Art Unit: 2814

Examiner: K. Eaton

7/2
4-8-99
G. Stanley

RESPONSE TO OFFICE ACTION OF OCTOBER 29, 1998

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Responsive to the office action of October 29, 1998, please
amend the captioned application as follows:

IN THE SPECIFICATION:

Please substitute the attached "Substitute Specification and
Abstract" for the originally filed specification and abstract.

IN THE CLAIMS:

Please cancel claims 1, 5, 7, 15 and 18 and add the following
new claims:

--21. A stress-adjusted insulating film forming method for forming
a multilayered insulating film on a substrate, said method

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